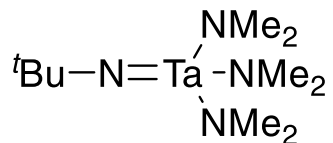


Catalog # 73-0700 t-Butylimidotris(dimethylamino)tantalum(V), min. 98%



Thermal Behavior:

- Melting point: 68-69°C [1, 2]

Technical Notes:

1. ALD/CVD precursor thin tantalum oxide film deposition.

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
T <sub>2</sub> O <sub>5</sub>	PE-ALD	-	-	PLO <sub>2</sub>	300°C	3, 4

References:

1. [J. Chem. Soc. Chem. Commun. 1978, 14, 579.](#)
2. [Inorg. Chem. 1983, 22, 965.](#)
3. [Semicond. Sci. Technol. 2013, 28, 082003.](#)
4. [ACS Appl. Mater. Interfaces 2016, 8, 22751.](#)